


APPLICATION DATA SHEET

Electronic Version v14

Stylesheet Version v14.0

Title of Invention	METHOD FOR REACTIVE ION ETCH PROCESSING OF A DUAL DAMASCENE STRUCTURE	
Application Type : regular, utility		
Attorney Docket Number : FIS920040053US1		
Correspondence address:		
Customer Number:	29371	
Inventors Information:		
<u>Inventor 1:</u>		
Applicant Authority Type:	Inventor	
Citizenship:	US	
Given Name:	William	
Middle Name:	G.	
Family Name:	America	
Residence:		
City of Residence:	Kingston	
State of Residence:	NY	
Country of Residence:	US	
Address-1 of Mailing Address:	243 City View Terrace	
Address-2 of Mailing Address:		
City of Mailing Address:	Kingston	
State of Mailing Address:	NY	
Postal Code of Mailing Address:	12401	
Country of Mailing Address:	US	
Phone:		
Fax:		
E-mail:		
<u>Inventor 2:</u>		
Applicant Authority Type:	Inventor	
Citizenship:	IN	
Given Name:	Kaushik	
Middle Name:	A.	

Family Name:	Kumar
Residence:	
City of Residence:	Beacon
State of Residence:	NY
Country of Residence:	US
Address-1 of Mailing Address:	14F South Lockey Woods Road
Address-2 of Mailing Address:	
City of Mailing Address:	Beacon
State of Mailing Address:	NY
Postal Code of Mailing Address:	12508
Country of Mailing Address:	US
Phone:	
Fax:	
E-mail:	

Assignee 1:

Organization Name:	International Business Machines Corporation
Address-1 of Mailing Address:	New Orchard Road
Address-2 of Mailing Address:	
City of Mailing Address:	Armonk
State of Mailing Address:	NY
Postal Code of Mailing Address:	12504
Country of Mailing Address:	US
Phone:	
Fax:	
E-mail:	